

1763#



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Won-Sung Choi )  
Serial No: 09/726,977 ) Art Unit 1763  
Filed: November 30, 2000 )  
For: THIN FILM DEPOSITION APPARATUS ) Examiner  
FOR SEMICONDUCTOR ) Kackar, Ram N.

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Commissioner for Patents  
Washington, D.C. 20231

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AMENDMENT UNDER 37 C.F.R. §1.111

Sir:

In response to the Office action dated April 16, 2002, please amend the above-identified application as follows:

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IN THE CLAIMS

Please cancel claim 4, without prejudice.

Please replace claims 1, 2, 5 and 11 with the following claims rewritten in clean form:

1. (Amended) A semiconductor thin film deposition apparatus comprising:
- at least one reactor in which a wafer is received;
  - a gas supply portion for supplying a reaction gas or inert gas to the reactor, wherein the gas supply portion includes:
    - at least one reaction gas supply unit for selectively providing the reaction gas to the reactor; and
    - an inert gas supply unit for providing the inert gas to the reactor;
  - an exhaust pump for exhausting gas from the reactor; and
  - an ozone supply portion for generating ozone to react with the reaction gas, wherein the ozone supply portion includes:
    - an ozone generator for generating the ozone;
    - at least one ozone transfer unit for transferring ozone to the reactor; and